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INFORMATION DISCLOSURE STATEMENT

Applicant	:	Hayashi et al.
App. No	:	Unknown
Filed	:	Herewith
For	:	RESIN FOR RESIST, POSITIVE RESIST COMPOSITION, AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Unknown
Art Unit	:	Unknown

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 20 references to be considered by the Examiner. Also enclosed are 15 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement. Please note that JP 07-234511 corresponds to U.S. 6,004,720; JP 09-73173 corresponds to U.S. 5,968,713; JP 09-90637 corresponds to U.S. 5,968,713; JP 10-161313 corresponds to U.S. 6,329,125; JP 10-319595 corresponds to U.S. 6,656,659; and JP 11-12326 corresponds to U.S. 6,887,644. The relevance of WO 2004/041879 A1 is that it is cited in the International Search Report from PCT priority application Serial No. PCT/JP2004/011735.

This Information Disclosure Statement is being filed within three months of the filing date, and no fee is required.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 24 Jan. 2006

By: Daniel Altman
Daniel E. Altman
Registration No. 34,115
Attorney of Record
Customer No. 20,995
(949) 760-0404

INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Multiple sheets used when necessary)</i>	Application No.	Unknown 10/565696
	Filing Date	Herewith
	First Named Inventor	Hayashi, Ryotaro
	Art Unit	Unknown
	Examiner	Unknown
SHEET 1 OF 1	Attorney Docket No.	SHIGA7.043APC

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
	1	6,004,720	12-21-1999	Takechi et al.	
	2	5,968,713	10-19-1999	Nozaki et al.	
	3	6,329,125 B2	12-11-2001	Takechi et al.	
	4	6,656,659	12-02-2003	Nozaki et al.	
	5	6,887,644 B1	05-03-2005	Nozaki et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹
	6	JP 2,881,969	02-05-1999	Fujitsu Ltd.		Abstract
	7	JP 05-346668	12-27-1993	Fujitsu Ltd.		Abstract
	8	JP 07-234511	09-05-1995			
	9	JP 09-73173	03-18-1997			
	10	JP 09-90637	04-04-1997			
	11	JP 10-161313	06-19-1998			
	12	JP 10-319595	12-04-1998			
	13	JP 11-12326	01-19-1999			
	14	JP 2004-300403	10-28-2004	JSR Corp.		Abstract
	15	JP 2004-176049	06-24-2004	JSR Corp.		Abstract
	16	JP 2003-280201	10-02-2003	JSR Corp.		Abstract
	17	JP 2003-238629	08-27-2003	Sumitomo Bakelite Co.		Abstract
	18	JP 2003-177538	06-27-2003	Fuji Photo Film Co. Ltd.		Abstract
	19	WO 2004/041879 A1	05-21-2004	JSR Corp.		
	20	JP 2003-223001	08-08-2003	Fuji Photo Film Co. Ltd.		Abstract

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹

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Examiner Signature	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

T¹ - Place a check mark in this area when an English language Translation is attached.